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Contents

KEYNOTE SESSION

11610 03 **Micro LED display: technology and manufacturing challenges (Keynote Paper)** [11610-41]

NANO IMPRINT

11610 05 **Nanoimprint performance improvements for high volume semiconductor device manufacturing (Invited Paper)** [11610-2]

11610 06 **Overlay models for nanoimprint lithography** [11610-3]

11610 07 **Addressing NIL integration for semiconductor device manufacturing** [11610-4]

11610 08 **Multi-field imprint technology: enabling the productivity enhancement of NIL** [11610-5]

11610 0C **Integration of sub 50 nm features based on EVG SmartNIL for 8-inch substrates** [11610-9]

ROLL TO ROLL

11610 0E **Design of a tomographic projection lithography process for roll-to-roll fabrication of 3D microstructures (Invited Paper)** [11610-11]

11610 0F **High-speed in-line optical angular scatterometer for high-throughput roll-to-roll nanofabrication (Invited Paper)** [11610-44]

OPTICAL DIRECT WRITING AND MASK WRITING: JOINT SESSION WITH CONFERENCES 11610 AND 11613

11610 0I **Direct laser writing on silicon surface for large area nanoplasmonic devices** [11610-14]

DSA II

11610 0O **Etch developments in response to DSA challenges (Invited Paper)** [11610-19]

EUV AND MBMW

- 11610 0Q **Multi-beam mask writer in EUV era: challenges and opportunities (Invited Paper)** [11610-21]
- 11610 0S **Curvilinear data format working group for MBMW era (Invited Paper)** [11610-23]

NOVEL OPTICAL AND EBEAM/ION

- 11610 0V **A novel method for generating linear structured illumination using phase modulation** [11610-26]
- 11610 0W **Processability of organic material for semiconductor packaging by 248 nm excimer laser**
[11610-27]
- 11610 0X **Practical fabrication methods for 3D origami structures from 2D films patterned via
photolithography** [11610-28]

TIP PATTERNING

- 11610 16 **Nanopositioning and fabrication using the Nano Fabrication Machine with a positioning range
up to Ø100 mm (Invited Paper)** [11610-35]
- 11610 1A **Single dopant atom lithography for the fabrication of quantum computers and low power
electronic devices** [11610-40]